

**PATENT APPLICATION**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q89627

Koichi TERASHIMA, et al.

Appln. No.: 10/544,783

Group Art Unit: 4135

Confirmation No.: 5339

Examiner: Pape A. SENE

Filed: August 8, 2005

For: METHOD FOR FORMING NICKEL SILICIDE FILM, METHOD FOR  
MANUFACTURING SEMICONDUCTOR DEVICE, AND METHOD FOR ETCHING  
NICKEL SILICIDE

**PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

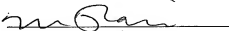
Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of April 29, 2008 to August 29, 2008.

The statutory fee of \$120.00 is being charged to Deposit Account No. 19-4880 via the EFS Payment Screen. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

SUGHRUE MION, PLLC  
Telephone: (202) 293-7060  
Facsimile: (202) 293-7860

  
Michael G. Raucci  
Registration No. 61,444

WASHINGTON OFFICE  
**23373**  
CUSTOMER NUMBER

Date: August 29, 2008